

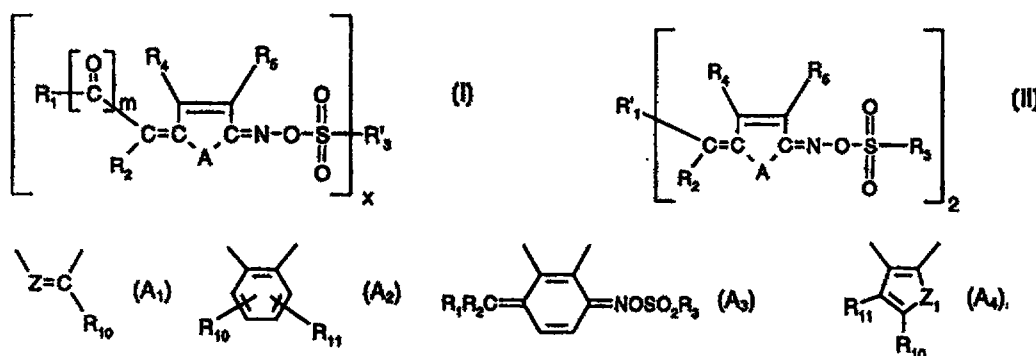


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(21) International Application Number: PCT/EP98/03750 (22) International Filing Date: 19 June 1998 (19.06.98) (30) Priority Data: 97810422.2 1 July 1997 (01.07.97) EP (34) Countries for which the regional or international application was filed: DE et al. (71) Applicant: CIBA SPECIALTY CHEMICALS HOLDING INC. [CH/CH]; Klybeckstrasse 141, CH-4057 Basel (CH). (72) Inventors: YAMATO, Hitoshi; 5-2-22-201, Nakayamasat-sukidai, Takarazuka, Hyogo 665 (JP). BLEIER, Hartmut; 3-14-12-401, Shinohara Kitamachi, Nada-ku, Kobe 657 (JP). BIRBAUM, Jean-Luc; 4-19-1-103, Mikage Yamate, Higashinada-ku, Kobe 658 (JP). KUNZ, Martin; Baslerstrasse 13/5, D-79588 Bfringen-Kirchen (DE). DIETLIKER, Kurt; Avenue Jean-Marie Musy 6, CH-1700 Fribourg (CH). DE LEO, Christoph; Marktplatz 3, D-79238 Ehrenkirchen (DE). ASAKURA, Toshikage; 4-8-1-102, Minoo, Minoo-shi, Osaka 562 (JP).		(81) Designated States: AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, CA, CH, CN, CU, CZ, DE, DK, EE, ES, FI, GB, GE, GH, GM, GW, HU, ID, IL, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MD, MG, MK, MN, MW, MX, NO, NZ, PL, PT, RO, RU, SD, SE, SG, SI, SK, SL, TJ, TM, TR, TT, UA, UG, UZ, VN, YU, ZW, ARIPO patent (GH, GM, KE, LS, MW, SD, SZ, UG, ZW), Eurasian patent (AM, AZ, BY, KG, KZ, MD, RU, TJ, TM), European patent (AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE), OAPI patent (BF, BJ, CF, CG, CI, CM, GA, GN, ML, MR, NE, SN, TD, TG). Published <i>With international search report.</i>

(54) Title: NEW OXIME SULFONATES AND THE USE THEREOF AS LATENT SULFONIC ACIDS**(57) Abstract**

New oximsulfonate compounds of formulae (I) or (II), wherein m is 0 or 1; x is 1 or 2; R₁ is, for example phenyl, which is unsubstituted or substituted or R₁ is a heteroaryl radical that is unsubstituted or substituted, or, if m is 0, R₁ additionally is C₂-C₆alkoxycarbonyl, phenoxycarbonyl or CN; R'₁ is for example C₂-C₁₂alkylene, phenylene; R₂ has for example one of the meanings of R₁; n is 1 or 2; R₃ is for example C₁-C₁₈alkyl, R'₃ when x is 1, has one of the meanings given for R₃, or R'₃ in formula (IV) and when x is 2 in formula (I), is for example C₂-C₁₂ alkylene, phenylene; R₄ and R₅ are independently of each other for example hydrogen, halogen, C₁-C₆alkyl; R₆ is for example hydrogen, phenyl; R₇ and R₈ are independently of each other for example hydrogen or C₁-C₁₂alkyl; R₉ is for example C₁-C₁₂alkyl; A is S, O, NR₆, or a group of formula (A1), (A2), (A3) or (A4); R₁₀ and R₁₁ independently of each other have one of the meanings given for R₄; R₁₂, R₁₃, R₁₄ and R₁₅ independently of one another are for example hydrogen, C₁-C₄alkyl; Z is CR₁₁ or N; Z₁ is -CH₂-, S, O or NR₆, are useful as latent sulfonic acids, especially in photoresist applications.